

L Number	Hits	Search Text	DB	Time stamp
1	5	941123.ap.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 13:36
2	26	titanium adj alloy near12 (zinc or zn or cadmium or cd or mercury or hg or aluminium or aluminum or al or gallium or ga or indium or tin or sn or silicon or si or germanium or ge or lead or pb or antimony or sb or as or arsenic) and memory and circuit and titanium adj silicide and (257/\$6.ccls. or 438/\$6.ccls. or 365/\$6.ccls.) and contact	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 13:47
3	2	("6284316").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 13:50
4	2	("6143362").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 16:45
5	62	(bpsg or (borophosphosilicate or boro-phosphosilicate or (boro-phospho-silicate or borophospho-silicate) adj glass)) and memory.ti,ab,clm. and (ti or titanium) near2 alloy and (257/\$6.ccls. or 438/\$6.ccls. or 365/\$6.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 16:52
6	19	(bpsg or (borophosphosilicate or boro-phosphosilicate or (boro-phospho-silicate or borophospho-silicate) adj glass)) and memory.ti,ab,clm. and (ti or titanium) near2 alloy and (257/\$6.ccls. or 438/\$6.ccls. or 365/\$6.ccls.) and titanium adj silicide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 17:56
7	61	memory.ti,ab,clm. and (ti or titanium) near2 alloy and (257/\$6.ccls. or 438/\$6.ccls. or 365/\$6.ccls.) and titanium adj silicide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 17:59

8	51	(US-6413812-\$ or US-6388284-\$ or US-6429449-\$ or US-6320213-\$ or US-6222273-\$ or US-6208016-\$ or US-5851882-\$ or US-5985698-\$ or US-6103612-\$ or US-6118135-\$ or US-6121086-\$ or US-6153490-\$ or US-6177314-\$ or US-6198151-\$ or US-6555431-\$ or US-6534781-\$ or US-6461957-\$ or US-6455875-\$ or US-6451665-\$ or US-5831276-\$ or US-5440158-\$ or US-5210047-\$ or US-5102827-\$ or US-5084418-\$ or US-4984196-\$ or US-4811078-\$).did. or (US-4636833-\$ or US-5495117-\$ or US-5483487-\$ or US-5475240-\$ or US-5580814-\$ or US-5745336-\$).did. or (US-20020182859-\$ or US-20020182858-\$ or US-20020177302-\$ or US-20020177292-\$ or US-20020123216-\$ or US-20020109233-\$ or US-20020079483-\$ or US-20020056862-\$ or US-20020031887-\$ or US-20020020835-\$ or US-20020003252-\$ or US-20010028082-\$ or US-20030030148-\$ or US-20030030147-\$ or US-20030006414-\$ or US-20010002708-\$ or US-20010001208-\$ or US-20010026960-\$ or US-20010022374-\$).did.	USPAT; US-PGPUB	2003/05/03 17:58
9	51	memory.ti,ab,clm. and (ti or titanium) near2 alloy and (257/\$6.ccls. or 438/\$6.ccls. or 365/\$6.ccls.) and titanium adj silicide and ((US-6413812-\$ or US-6388284-\$ or US-6429449-\$ or US-6320213-\$ or US-6222273-\$ or US-6208016-\$ or US-5851882-\$ or US-5985698-\$ or US-6103612-\$ or US-6118135-\$ or US-6121086-\$ or US-6153490-\$ or US-6177314-\$ or US-6198151-\$ or US-6555431-\$ or US-6534781-\$ or US-6461957-\$ or US-6455875-\$ or US-6451665-\$ or US-5831276-\$ or US-5440158-\$ or US-5210047-\$ or US-5102827-\$ or US-5084418-\$ or US-4984196-\$ or US-4811078-\$).did. or (US-4636833-\$ or US-5495117-\$ or US-5483487-\$ or US-5475240-\$ or US-5580814-\$ or US-5745336-\$).did. or (US-20020182859-\$ or US-20020182858-\$ or US-20020177302-\$ or US-20020177292-\$ or US-20020123216-\$ or US-20020109233-\$ or US-20020079483-\$ or US-20020056862-\$ or US-20020031887-\$ or US-20020020835-\$ or US-20020003252-\$ or US-20010028082-\$ or US-20030030148-\$ or US-20030030147-\$ or US-20030006414-\$ or US-20010002708-\$ or US-20010001208-\$ or US-20010026960-\$ or US-20010022374-\$).did.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 19:17
10	13	Ti-Al-N near6 alloy	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 19:35
11	678	(257/754).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 19:35
12	2	((257/754).CCLS.) and (titanium adj silicide or "ti si.sub.2") and titanium near6 alloy and memory.ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 19:36

-	140	(257/486).CCLS.	USPAT;	2003/05/03
-	203	((257/642) or (257/643)).CCLS.	US-PGPUB	13:22
-	36	(257/645).CCLS.	USPAT;	2001/09/27
-	53	(257/651).CCLS.	US-PGPUB	11:18
-	612	(257/751).CCLS.	USPAT;	2001/09/27
-	278	(257/752).CCLS.	US-PGPUB	11:19
-	182	(257/753).CCLS.	USPAT;	2001/09/27
-	389	(257/754).CCLS.	US-PGPUB	11:19
-	210	(257/757).CCLS.	USPAT;	2001/09/27
-	194	(257/759).CCLS.	US-PGPUB	11:20
-	307	(257/760).CCLS.	USPAT;	2001/09/27
-	155	(257/761).CCLS.	US-PGPUB	11:20
-	251	(257/765).CCLS.	USPAT;	2001/09/27
-	371	(257/766).CCLS.	US-PGPUB	11:20
-	234	(257/767).CCLS.	USPAT;	2001/09/27
-	251	(257/768).CCLS.	US-PGPUB	11:21
-	248	(257/770).CCLS.	USPAT;	2001/09/27
-	132	(257/642).CCLS.	US-PGPUB	11:21
-	97	(257/643).CCLS.	USPAT;	2001/09/27
-	36	(257/645).CCLS.	US-PGPUB	11:21
-	53	(257/651).CCLS.	USPAT;	2001/09/27
-	985	(257/758).CCLS.	US-PGPUB	11:21
-	2061	((("257/486").CCLS.) or ((("257/642") or ("257/643").CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/751").CCLS.) or ("257/752").CCLS.) or ("257/753").CCLS.) or ("257/754").CCLS.) or ("257/757").CCLS.) or ("257/759").CCLS.) or ("257/760").CCLS.)	USPAT;	2001/09/27
-	2341	((("257/761").CCLS.) or ("257/765").CCLS.) or ("257/766").CCLS.) or ("257/767").CCLS.) or ("257/768").CCLS.) or ("257/770").CCLS.) or ("257/642").CCLS.) or ("257/643").CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/758").CCLS.)	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	11:23
-			USPAT;	2001/09/27
-			US-PGPUB;	11:24
-			EPO; JPO;	
-			DERWENT;	
-			IBM_TDB	

-	369	(((("257/486").CCLS.) or (((("257/642") or ("257/643")).CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/751").CCLS.) or ("257/752").CCLS.) or ("257/753").CCLS.) or ("257/754").CCLS.) or ("257/757").CCLS.) or ("257/759").CCLS.) or ("257/760").CCLS.) or (((("257/761").CCLS.) or ("257/765").CCLS.) or ("257/766").CCLS.) or ("257/767").CCLS.) or ("257/768").CCLS.) or ("257/770").CCLS.) or ("257/642").CCLS.) or ("257/643").CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/758").CCLS.))) and fluorin\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 11:25
-	554	fluorin\$4 and integrated adj circuit	EPO; JPO; DERWENT; IBM_TDB	2001/09/27 11:26
-	65	((((("257/486").CCLS.) or (((("257/642") or ("257/643")).CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/751").CCLS.) or ("257/752").CCLS.) or ("257/753").CCLS.) or ("257/754").CCLS.) or ("257/757").CCLS.) or ("257/759").CCLS.) or ("257/760").CCLS.) or (((("257/761").CCLS.) or ("257/765").CCLS.) or ("257/766").CCLS.) or ("257/767").CCLS.) or ("257/768").CCLS.) or ("257/770").CCLS.) or ("257/642").CCLS.) or ("257/643").CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/758").CCLS.))) and fluorin\$4) or (fluorin\$4 and integrated adj circuit)) and substrate and (silicon same (tantalum or tantalum adj nitride or tantalum adj silicide or cobalt or cobalt adj silicide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 13:35
-	33	((("6281584") or ("6277730") or ("6274933") or ("6262485") or ("6211561") or ("6157081") or ("6097095") or ("5719416") or ("5675185") or ("5668394") or ("5585673") or ("5306951") or ("5138432") or ("4675073")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 13:36
-	2	jp-11354464\$-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 13:37
-	35	((("6281584") or ("6277730") or ("6274933") or ("6262485") or ("6211561") or ("6157081") or ("6097095") or ("5719416") or ("5675185") or ("5668394") or ("5585673") or ("5306951") or ("5138432") or ("4675073")).PN.) or jp-11354464\$-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 13:44

-	8	((("6281584") or ("6277730") or ("6274933") or ("6262485") or ("6211561") or ("6157081") or ("6097095") or ("5719416") or ("5675185") or ("5668394") or ("5585673") or ("5306951") or ("5138432") or ("4675073")).PN.) or jp-11354464\$-\$.did.) and (fluorine near10 barrier)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 13:44
-	1	6277730.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 16:39
-	320	fluorine adj2 silicon adj (oxide or dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 16:41
-	87	fluorine adj2 silicon adj dioxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 16:46
-	245	fluorine adj2 silicon adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 16:51
-	1	6281584.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 17:14
-	0	fluorinated adj silicon adj dioxide adj "(sio"\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 17:17
-	275	"(sio\$3)"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 17:19
-	7	"(sio\$3)" and fluorinated	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 17:26
-	183	silicon adj monoxide and 257/\$5.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 17:27
-	14	silicon adj monoxide.ti,ab. and 257/\$5.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 17:28
-	0	(fluorinated near10 silicon adj monoxide) and 257/\$5.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 17:28
-	56	fsg adj film	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 17:42

-	3	fsg adj film same dioxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 17:42
-	2	jp-10035152\$-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/27 20:23
-	0	yuasa.in. and fluorine and interconnect	JPO	2001/09/27 20:23
-	0	yuasa.in. and fluorine and barrier	JPO	2001/09/27 20:23
-	27	yuasa.in. and fluorine	JPO	2001/09/27 20:26
-	28	yuasa.in. and fluorine	JPO; DERWENT	2001/09/27 20:26
-	1	yuasa.in. and fluorine	DERWENT	2001/09/27 20:27
-	0	yuasa.in. and "035152"	JPO	2001/09/27 20:28
-	1	yuasa.in. and fluorine	DERWENT	2001/09/27 20:28
-	1	6281584.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 10:11
-	5205	((("257/486").CCLS.) or ((("257/642") or ("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or (("257/761").CCLS.) or (("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 10:28

-	6	(((("257/486").CCLS.) or (((("257/642") or ("257/643")).CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/751").CCLS.) or ("257/752").CCLS.) or ("257/753").CCLS.) or ("257/754").CCLS.) or ("257/757").CCLS.) or ("257/759").CCLS.) or ("257/760").CCLS.) or (((("257/761").CCLS.) or ("257/765").CCLS.) or ("257/766").CCLS.) or ("257/767").CCLS.) or ("257/768").CCLS.) or ("257/770").CCLS.) or ("257/642").CCLS.) or ("257/643").CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/758").CCLS.))) and fluorine adj2 barrier	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 10:39
-	0	(((("257/486").CCLS.) or (((("257/642") or ("257/643")).CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/751").CCLS.) or ("257/752").CCLS.) or ("257/753").CCLS.) or ("257/754").CCLS.) or ("257/757").CCLS.) or ("257/759").CCLS.) or ("257/760").CCLS.) or (((("257/761").CCLS.) or ("257/765").CCLS.) or ("257/766").CCLS.) or ("257/767").CCLS.) or ("257/768").CCLS.) or ("257/770").CCLS.) or ("257/642").CCLS.) or ("257/643").CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/758").CCLS.))) and fluorine adj1 barrier same tasin	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 10:40
-	0	(((("257/486").CCLS.) or (((("257/642") or ("257/643")).CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/751").CCLS.) or ("257/752").CCLS.) or ("257/753").CCLS.) or ("257/754").CCLS.) or ("257/757").CCLS.) or ("257/759").CCLS.) or ("257/760").CCLS.) or (((("257/761").CCLS.) or ("257/765").CCLS.) or ("257/766").CCLS.) or ("257/767").CCLS.) or ("257/768").CCLS.) or ("257/770").CCLS.) or ("257/642").CCLS.) or ("257/643").CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/758").CCLS.))) and (fluorine adj1 barrier and tasin)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 10:40

-	2	((((("257/486").CCLS.) or (((("257/642") or ("257/643")).CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or ((((("257/761").CCLS.) or ("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.)))) and (fluorine adj1 barrier and (tasin or tantalum))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 10:42
-	2	((((("257/486").CCLS.) or (((("257/642") or ("257/643")).CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or ((((("257/761").CCLS.) or ("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.)))) and (fluorine adj1 barrier and (tasin or tantalum)) and (@rlad<20000414)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 10:49
-	0	((((("257/486").CCLS.) or (((("257/642") or ("257/643")).CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or ((((("257/761").CCLS.) or ("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.)))) and (fluorine adj1 barrier same (tasin or tantalum or cobalt or silicide)) and (@rlad<20000414)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 10:50

-	0	((((("257/486").CCLS.) or (((("257/642") or ("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or ((((("257/761").CCLS.) or (("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.))) and (fluorine adj2 barrier same (tasin or tantalum or cobalt or silicide)) and (@rlad<20000414) 0	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 10:51
-	0	((((("257/486").CCLS.) or (((("257/642") or ("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or ((((("257/761").CCLS.) or (("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.))) and (fluorine adj2 barrier same (tasin or tantalum or cobalt or silicide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 10:51

-	4	((("257/486").CCLS.) or ((("257/642") or ("257/643")).CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/751").CCLS.) or ("257/752").CCLS.) or ("257/753").CCLS.) or ("257/754").CCLS.) or ("257/757").CCLS.) or ("257/759").CCLS.) or ("257/760").CCLS.) or ((("257/761").CCLS.) or ("257/765").CCLS.) or ("257/766").CCLS.) or ("257/767").CCLS.) or ("257/768").CCLS.) or ("257/770").CCLS.) or ("257/642").CCLS.) or ("257/643").CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/758").CCLS.))) and (fluorine same diffusion adj barrier same (tasin or tantalum or cobalt or silicide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 11:09
-	11	((("257/486").CCLS.) or ((("257/642") or ("257/643")).CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/751").CCLS.) or ("257/752").CCLS.) or ("257/753").CCLS.) or ("257/754").CCLS.) or ("257/757").CCLS.) or ("257/759").CCLS.) or ("257/760").CCLS.) or ((("257/761").CCLS.) or ("257/765").CCLS.) or ("257/766").CCLS.) or ("257/767").CCLS.) or ("257/768").CCLS.) or ("257/770").CCLS.) or ("257/642").CCLS.) or ("257/643").CCLS.) or ("257/645").CCLS.) or ("257/651").CCLS.) or ("257/758").CCLS.))) and (fluorine same diffusion adj barrier same (tasin or tantalum or cobalt or silicide or silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 11:10
-	2	6265779.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 13:24
-	0	(graded near5 diffusion adj barrier) and fluorin\$4 and dielectric and (integrated adj circuit or semiconductor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 14:34
-	0	(graded near5 diffusion adj barrier) and fluorin\$4 and dielectric and (integrated adj circuit or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 14:35
-	0	(graded near5 (diffusion adj barrier or cap\$4 adj (layer or film))) and fluorin\$4 and dielectric and (integrated adj circuit or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 14:37

-	364	graded and fluorin\$ and barrier	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 14:37
-	209	graded and fluorin\$ and barrier and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 14:38
-	70	graded and fluorin\$ and barrier and silicon and (tantalum or cobalt)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 14:39
-	34	graded and fluorin\$ and barrier and silicon and (tantalum or cobalt) and @rlad<20000414	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 14:39
-	34	graded and fluorin\$ and barrier and silicon and (tantalum or cobalt) and @rlad<20000404	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 14:40
-	15	graded and fluorin\$ and barrier and silicon and (tantalum or cobalt) and @rlad<20000404 and (257/\$5.ccls. or 438/\$5.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 15:00
-	0	graded and fluorin\$ and barrier and silicon and (tantalum or cobalt) and @rlad<20000404 and (dielectric and substrate)	EPO; JPO; DERWENT; IBM_TDB	2001/09/28 15:01
-	0	graded and fluorin\$ and barrier and silicon and (tantalum or cobalt) and (dielectric and substrate)	EPO; JPO; DERWENT; IBM_TDB	2001/09/28 15:01
-	0	graded adj barrier and 257/\$5.ccls. and (fluorin\$4 nearl0 dielectric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 15:42
-	33	graded adj2 barrier and 257/\$5.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 15:42
-	1	graded adj2 barrier and 257/\$5.ccls. and fluorin\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 16:04
-	0	57720527.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 15:56
-	3	5770520.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 15:56
-	74777	graded adj barrier layer and 257/\$5.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 16:05

-	1	graded adj barrier adj layer.ti. and 257/\$5.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 16:22
-	0	graded adj barrier and fluorin\$2	EPO; JPO; DERWENT; IBM_TDB	2001/09/28 16:29
-	0	graded adj tantalum adj silicide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 16:31
-	13	(silicon near10 tantalum) same graded	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 16:32
-	7	((silicon near10 tantalum) same graded) and barrier	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 16:33
-	242	(tantalum near5 silicon) same (barrier or cap\$4) adj2 (layer or film)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 16:57
-	46	(tantalum near5 silicon) same (barrier or cap\$4) adj2 (layer or film) and 257/\$5.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 17:04
-	0	(tantalum near5 silicon) same (barrier or cap\$4) adj2 (layer or film) and 257/\$5.ccls and fluorin\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 17:05
-	33	(tantalum near5 silicon) same (barrier or cap\$4) adj2 (layer or film) and fluorin\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 17:06
-	2	(tantalum near5 silicon) same (barrier or cap\$4) adj2 (layer or film) same fluorin\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/28 17:07
-	0	(barrier or capping or cap) adj (layer adj film adj region)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:46
-	60203	(barrier or capping or cap) adj (layer or film or region)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:47
-	11894	((barrier or capping or cap) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:55
-	3818	((barrier or capping or cap) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls.) and (silicon near10 (barrier or capping or cap))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:58

-	416	(((((barrier or capping or cap) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls.)) and (silicon near10 (barrier or capping or cap))) and (tantalum or cobalt) near10 (barrier or capping or cap))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:59
-	1	(((((barrier or capping or cap) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls.)) and (silicon near10 (barrier or capping or cap))) and (tantalum or cobalt) near10 (barrier or capping or cap)) and (fluorin\$4 near (barrier or cap or capping))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:59
-	12200	((barrier or capping or cap) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls. or 313/\$5.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:56
-	3862	((barrier or capping or cap) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls. or 313/\$5.ccls.)) and (silicon near10 (barrier or capping or cap))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:56
-	420	(((((barrier or capping or cap) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls. or 313/\$5.ccls.)) and (silicon near10 (barrier or capping or cap))) and (tantalum or cobalt) near10 (barrier or capping or cap))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:57
-	1	(((((barrier or capping or cap) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls. or 313/\$5.ccls.)) and (silicon near10 (barrier or capping or cap))) and (tantalum or cobalt) near10 (barrier or capping or cap)) and (fluorin\$4 near (barrier or cap or capping))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:57
-	6939	((barrier or capping or cap) adj (layer or film or region)) and (silicon near10 (barrier or capping or cap))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:58
-	552	((barrier or capping or cap) adj (layer or film or region)) and (silicon near10 (barrier or capping or cap))) and (tantalum or cobalt) near10 (barrier or capping or cap)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 18:59
-	16	((barrier or capping or cap) adj (layer or film or region)) and (silicon near10 (barrier or capping or cap))) and (silicon near10 (barrier or capping or cap)) and (fluorin\$4 near (barrier or cap or capping))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 19:01
-	1	(((((barrier or capping or cap) adj (layer or film or region)) and (silicon near10 (barrier or capping or cap))) and (tantalum or cobalt) near10 (barrier or capping or cap)) and (fluorin\$4 near (barrier or cap or capping))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 19:01
-	0	(graded near4 (cap or capping or barrier)) and (fluorin\$4 near4 (barrier or cap or capping)) and (silicon near4 (barrier or cap or capping)) and ((tantalum or cobalt) near4 (barrier or cap or capping))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 19:08
-	2	(fluorin\$4 near4 (barrier or cap or capping)) and (silicon near4 (barrier or cap or capping)) and ((tantalum or cobalt) near4 (barrier or cap or capping))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 20:07

-	1483	(adhesion or adhesive or bonding) same ((barrier or cap or capping) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 20:11
-	534	(adhesion or adhesive or bonding) adj (layer or film or region) same ((barrier or cap or capping) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 20:12
-	106	(adhesion or adhesive or bonding) adj (layer or film or region) same ((barrier or cap or capping) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls.) and fluorin\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 20:14
-	27	(adhesion or adhesive or bonding) adj (layer or film or region) same ((barrier or cap or capping) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls.) and (fluorin\$4 same barrier)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 20:15
-	19	(adhesion or adhesive or bonding) adj (layer or film or region) same ((barrier or cap or capping) adj (layer or film or region)) and (257/\$5.ccls. or 438/\$5.ccls.) and (fluorin\$4 same (barrier or cap or capping) adj (layer or film or region)) and ((tantalum or silicon or cobalt) near10 (barrier or cap or capping))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/29 20:18
-	1	6277730.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 15:24
-	1	6281584.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 19:26
-	1	6252303.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 16:07
-	0	(257/\$5.ccls. or 438/\$5.ccls.) and depleted same fluorine same barrier same adhesi\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 17:24
-	48	((("5946601") or ("6281584") or ("6252303") or ("6022766") or ("6287990") or ("5675185") or ("6277730") or ("6274933") or ("6262485") or ("6211561") or ("6157081") or ("5138432") or ("6097095") or ("5719416") or ("5668394") or ("5585673") or ("5306951") or ("4675073") or ("6265779") or ("6184550") or ("6265779") or ("5942769") or ("6284657") or ("6054398")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 19:03
-	23	((("5946601") or ("6281584") or ("6252303") or ("6022766") or ("6287990") or ("5675185") or ("6277730") or ("6274933") or ("6262485") or ("6211561") or ("6157081") or ("5138432") or ("6097095") or ("5719416") or ("5668394") or ("5585673") or ("5306951") or ("4675073") or ("6265779") or ("6184550") or ("6265779") or ("5942769") or ("6284657") or ("6054398")).PN.	USPAT	2001/09/30 19:03

-	18	((("5946601") or ("6281584") or ("6252303") or ("6022766") or ("6287990") or ("5675185") or ("6277730") or ("6274933") or ("6262485") or ("6211561") or ("6157081") or ("5138432") or ("6097095") or ("5719416") or ("5668394") or ("5585673") or ("5306951") or ("4675073") or ("6265779") or ("6184550") or ("6265779") or ("5942769") or ("6284657") or ("6054398")).PN.) and interconnect\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 19:03
-	14	((("5946601") or ("6281584") or ("6252303") or ("6022766") or ("6287990") or ("5675185") or ("6277730") or ("6274933") or ("6262485") or ("6211561") or ("6157081") or ("5138432") or ("6097095") or ("5719416") or ("5668394") or ("5585673") or ("5306951") or ("4675073") or ("6265779") or ("6184550") or ("6265779") or ("5942769") or ("6284657") or ("6054398")).PN.) and (interconnect\$3 same (copper or aluminum or aluminium or tungsten or molybdenum or silver or gold or tantalum adj nitride or titanium adj nitride))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 19:10
-	3	((("5946601") or ("6281584") or ("6252303") or ("6022766") or ("6287990") or ("5675185") or ("6277730") or ("6274933") or ("6262485") or ("6211561") or ("6157081") or ("5138432") or ("6097095") or ("5719416") or ("5668394") or ("5585673") or ("5306951") or ("4675073") or ("6265779") or ("6184550") or ("6265779") or ("5942769") or ("6284657") or ("6054398")).PN.) and (interconnect\$3 same (copper or aluminum or aluminium or tungsten or molybdenum or silver or gold or tantalum adj nitride or titanium adj nitride) same (fsg or fluorosilicate or fluorinated) same (barrier or cap or capping or passivation))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 19:12
-	723	(257/\$5.ccls. or 438/\$5.ccls.) and fluorin\$4 and (barrier or passivation or passivated or cap or capping) and (dielectric or capacitance) and (interconnect\$3 same (copper or aluminum or aluminum or tungsten or molybdenum or silver or gold or titanium adj nitride or tantalum adj nitride))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 19:31
-	192	(257/\$5.ccls. or 438/\$5.ccls.) and (fluorin\$4 same (barrier or passivation or passivated or cap or capping)) and (dielectric or capacitance) and (interconnect same (copper or aluminium or aluminum or tungsten or molybdenum or silver or gold or titanium adj nitride or tantalum adj nitride))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 19:32
-	17	(257/758.ccls.) and (fluorin\$4 same (barrier or passivation or passivated or cap or capping)) and (dielectric or capacitance) and (interconnect same (copper or aluminium or aluminum or tungsten or molybdenum or silver or gold or titanium adj nitride or tantalum adj nitride))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2001/09/30 19:33

-	6931	((((("257/486").CCLS.) or ((("257/642") or ("257/643")).CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or ((((("257/761").CCLS.) or (("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.))) and fluorin\$4) or (fluorin\$4 and integrated adj circuit) 564 (((((((("257/486").CCLS.) or ((("257/642") or ("257/643")).CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or ((((("257/761").CCLS.) or (("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.))) and fluorin\$4) or (fluorin\$4 and integrated adj circuit)) and (fluorin\$4 near3 polymer\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 09:15
-	564	((((("257/486").CCLS.) or ((("257/642") or ("257/643")).CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or ((((("257/761").CCLS.) or (("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.))) and fluorin\$4) or (fluorin\$4 and integrated adj circuit)) and (fluorin\$4 near3 polymer\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 09:17

-	63	((((("257/486").CCLS.) or (("257/642") or ("257/643")).CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or (("257/761").CCLS.) or (("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.))) and fluorin\$4) or (fluorin\$4 and integrated adj circuit)) and (fluorin\$4 near3 polymer\$2)) and (barrier near3 diffusion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 09:24
-	25	((((("257/486").CCLS.) or (("257/642") or ("257/643")).CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/751").CCLS.) or (("257/752").CCLS.) or (("257/753").CCLS.) or (("257/754").CCLS.) or (("257/757").CCLS.) or (("257/759").CCLS.) or (("257/760").CCLS.) or (("257/761").CCLS.) or (("257/765").CCLS.) or (("257/766").CCLS.) or (("257/767").CCLS.) or (("257/768").CCLS.) or (("257/770").CCLS.) or (("257/642").CCLS.) or (("257/643").CCLS.) or (("257/645").CCLS.) or (("257/651").CCLS.) or (("257/758").CCLS.))) and fluorin\$4) or (fluorin\$4 and integrated adj circuit)) and (fluorin\$4 near3 polymer\$2)) and (barrier near3 diffusion)) and diffusion adj barrier and polymer\$2 near3 dielectric and (ic or integrated adj circuit)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 11:57
-	8	diffusion adj barrier near6 polymer\$2 near6 dielectric and (ic or integrated adj circuit)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 12:07
-	5	(diffusion adj barrier near6 polymer\$2 near6 dielectric and (ic or integrated adj circuit)) and (bcb or benzocyclobutane or benzocyclobutene or cyclotene or poly adj arylene adj ether or poly-arylene adj ether or silk or polyimide or aromatic adj hydrocarbon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 12:14

-	2	(diffusion adj barrier near6 polymer\$2 near6 dielectric and (ic or integrated adj circuit)) and ((bcb or benzocyclobutarene or benzocyclobutene or cyclotene or poly adj arylene adj ether or poly-arylene adj ether or silk or polyimide or aromatic adj hydrocarbon) same barrier adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 12:17
-	767	((bcb or benzocyclobutarene or benzocyclobutene or cyclotene or poly adj arylene adj ether or poly-arylene adj ether or silk or polyimide or aromatic adj hydrocarbon) same barrier adj layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 12:18
-	32	((bcb or benzocyclobutarene or benzocyclobutene or cyclotene or poly adj arylene adj ether or poly-arylene adj ether or silk or polyimide or aromatic adj hydrocarbon) with barrier adj layer) and integrated adj circuit.ti,ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 12:20
-	0	((bcb or benzocyclobutarene or benzocyclobutene or cyclotene or poly adj arylene adj ether or poly-arylene adj ether or silk or polyimide or aromatic adj hydrocarbon) with barrier adj layer with fluorinated) and integrated adj circuit.ti,ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 12:20
-	8	((bcb or benzocyclobutarene or benzocyclobutene or cyclotene or poly adj arylene adj ether or poly-arylene adj ether or silk or polyimide or aromatic adj hydrocarbon) with barrier adj layer with fluorinated)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 12:21
-	7	((bcb or benzocyclobutarene or benzocyclobutene or cyclotene or poly adj arylene adj ether or poly-arylene adj ether or silk or polyimide or aromatic adj hydrocarbon) with barrier adj layer with fluorinated) and (257/\$6.ccls. or 438/\$6.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 12:30
-	22	((pfcb or perfluorocyclobutane or fluorinated polyethylene or ptfe or polytetrafluoroethylene or fluorinated adj parylene) with barrier adj layer with fluorinated) and (257/\$6.ccls. or 438/\$6.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 13:44
-	2	("6284657").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 15:53
-	39	parylene-F	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 16:02
-	9	(parylene-F or af-4 or polytetrafluoro-p-xylylene) same dielectric adj layer and (257/\$6.ccls. or 438/\$6.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 16:56
-	2	(graded near6 (barrier adj (film or layer))) same silicon same (ta or tantalum or tantalum adj nitride or tan\$3 or tantalum adj silicide or tasi\$3 or cobalt or cobalt adj silicide or co or cosi\$3) and (integrated adj circuit or 257/\$6.ccls. or 438/\$6.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 17:04

-	2	((graded near6 (barrier adj (film or layer))) same silicon same (ta or tantalum or tantalum adj nitride or tan\$3 or tantalum adj silicide or tasi\$3 or cobalt or cobalt adj silicide or co or cosi\$3) and (integrated adj circuit or ic)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 17:05
-	5	((graded near12 (barrier adj (film or layer))) near12 silicon) and (ta or tantalum or tantalum adj nitride or tan\$3 or tantalum adj silicide or tasi\$3 or cobalt or cobalt adj silicide or co or cosi\$3) and (integrated adj circuit or ic)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:00
-	0	((graded near12 (barrier adj (film or layer))) near12 silicon) and (ta or tantalum or tantalum adj nitride or tan\$3 or tantalum adj silicide or tasi\$3 or cobalt or cobalt adj silicide or co or cosi\$3) and (integrated adj circuit or ic) and plurality	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:02
-	31	low-k adj dielectric and polymer\$2 and barrier adj (layer or film) and ((plurality near3 layer) or (alternat\$3 near3 (layer or film)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:04
-	25	low-k adj dielectric and polymer\$2 and barrier adj (layer or film) and ((plurality near3 layer) or (alternat\$3 near3 (layer or film))) and integrated adj circuit	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:15
-	1	("6281584").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:19
-	0	("adhesion adj layer same barrier adj layer same low-k adj dielectric").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:20
-	3	adhesion adj layer same barrier adj layer same low-k adj dielectric	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:21
-	29	adhesion adj layer and barrier adj layer and low-k adj dielectric	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:22
-	0	(adhesion adj layer near20 barrier adj layer) near20 low-k adj dielectric	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:22
-	6	(adhesion adj layer near20 barrier adj layer) and low-k adj dielectric	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:32
-	0	(adhesion adj layer near20 cobalt adj silicide) and low-k adj dielectric	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 21:44
-	2	("6323555").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/19 22:31

-	3	((("6258732") or ("6017818") or ("6323555"))).PN.	USPAT	2002/04/19 22:32
-	60	(fluorine or f or fluorinated) near4 dielectric same (fluorine of f) near4 barrier	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 09:26
-	39	(fluorine or f or fluorinated) near4 dielectric same (fluorine of f) near4 barrier and (semiconductor or interconnect or integrated near2 circuit).ti,ab,clm.	USPAT; US-PGPUB	2002/09/27 09:55
-	28	(fluorine or f or fluorinated) near4 dielectric same (fluorine of f) near4 barrier and (semiconductor or interconnect or integrated near2 circuit).ti,ab,clm. and (tantalum or cobalt)	USPAT; US-PGPUB	2002/09/27 09:56
-	2	(fluorine or f or fluorinated) near4 dielectric same (fluorine of f) near4 barrier same (tantalum or cobalt) and (semiconductor or interconnect or integrated near2 circuit).ti,ab,clm.	USPAT; US-PGPUB	2002/09/27 10:50
-	0	(fluorine or f or fluorinated) near4 dielectric same (fluorine of f) near4 barrier same (tantalum or cobalt) and (semiconductor or interconnect or integrated near2 circuit).ti,ab,clm.	EPO; JPO; DERWENT; IBM_TDB	2002/09/27 10:51
-	0	(fluorine or f or fluorinated) near12 dielectric near12 (fluorine of f) near12 barrier same (tantalum or cobalt) and (semiconductor or interconnect or integrated near2 circuit).ti,ab,clm.	EPO; JPO; DERWENT; IBM_TDB	2002/09/27 10:52
-	0	(fluorine or f or fluorinated) near12 dielectric near12 (fluorine of f) near12 barrier near12 (tantalum or cobalt) and (semiconductor or interconnect or integrated near2 circuit).ti,ab,clm.	EPO; JPO; DERWENT; IBM_TDB	2002/09/27 10:52
-	4	(fluorine or f or fluorinated) near12 dielectric near12 (fluorine of f) near12 barrier near12 (tantalum or cobalt) and (semiconductor or interconnect or integrated near2 circuit).ti,ab,clm.	USPAT; US-PGPUB	2002/09/27 11:13
-	4	(fluorine or f or fluorinated) near12 (insulat\$3 or dielectric) near12 (fluorine of f) near12 barrier near12 (tantalum or cobalt) and (semiconductor or interconnect or integrated near2 circuit).ti,ab,clm.	USPAT; US-PGPUB	2002/09/27 11:14
-	4	((fluorine or f or fluorinated) near12 (insulat\$3 or dielectric)) or F-BPSG or fluorinated adj boro-phospho adj silicate adj glass) near12 (fluorine of f) near12 barrier near12 (tantalum or cobalt) and (semiconductor or interconnect or integrated near2 circuit).ti,ab,clm.	USPAT; US-PGPUB	2002/09/27 11:18
-	5	((fluorine or f or fluorinated) near12 (insulat\$3 or dielectric)) or F-BPSG or fluorinated adj boro-phospho adj silicate adj glass) near12 barrier near12 (tantalum or cobalt) and (semiconductor or interconnect or integrated near2 circuit).ti,ab,clm.	USPAT; US-PGPUB	2002/09/27 11:19
-	39	(fluorinated adj dielectric or F-BPSG or fluorinated adj boro-phospho adj silicate adj glass).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 11:21

-	0	((fluorinated adj dielectric or F-BPSG or fluorinated adj boro-phospho adj silicate adj glass).ti,ab,clm.) and barrier near12 (cobalt adj silicide or tantalum adj silicide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 11:23
-	14	((fluorinated adj dielectric or F-BPSG or fluorinated adj boro-phospho adj silicate adj glass).ti,ab,clm.) and barrier near2 layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 11:23
-	8	((fluorinated adj dielectric or F-BPSG or fluorinated adj boro-phospho adj silicate adj glass).ti,ab,clm.) and barrier near2 layer) and (cobalt or tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 12:46
-	0	tantalum adj (silicide or salicide) near12 barrier near12 fluorine	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 12:48
-	0	tantalum-silicon-nitride near12 barrier near12 fluorine	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 12:49
-	3	tantalum-silicon-nitride near12 barrier	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:03
-	15	diffusion near4 fluorine adj ions	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 12:54
-	0	(cobalt or cobalt-silicon or cobalt-tantalum-silicon or cobalt-tantalum or tantalum-cobalt or tantalum) near12 diffusion adj layer near12 fluorine	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:06
-	156	(cobalt or cobalt-silicon or cobalt-tantalum-silicon or cobalt-tantalum or tantalum-cobalt or tantalum) near12 diffusion adj layer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:10
-	52	(cobalt or cobalt-silicon or cobalt-tantalum-silicon or cobalt-tantalum or tantalum-cobalt or tantalum) near12 diffusion adj layer.ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:11
-	21	(cobalt adj silicide or cobalt-silicon or cobalt-tantalum-silicon or cobalt-tantalum or tantalum-cobalt or tantalum adj silicide) near12 diffusion adj layer.ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:12
-	9	(cobalt adj silicide or cobalt-silicon or cobalt-tantalum-silicon or cobalt-tantalum or tantalum-cobalt or tantalum adj silicide) near12 barrier adj layer.ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:31
-	1	(cobalt adj silicide or cobalt-silicon or cobalt-tantalum-silicon or cobalt-tantalum or tantalum-cobalt or tantalum adj silicide) near12 barrier adj layer.ti,ab,clm. and fluorine	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:28
-	4	cobalt adj silicide near10 fluorinated	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:32

-	5	tantalum adj silicide near10 fluorinated	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:38
-	0	(ta-si or tantalum-silicon) near10 fluorinated	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:39
-	0	(ta-si or tantalum-silicon) near10 (fluorinated or fsg)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 14:41
-	0	(co-si or tantalum-silicon) near10 (fluorinated or fsg)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 15:58
-	90	capping adj layer near12 (adhesion or adhesive)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 15:59
-	64	capping adj layer near12 (adhesion or adhesive)	USPAT	2002/09/27 16:12
-	5	(nucleation or adhesion or adhesive or adhesion-promoting) adj2 (film or layer) same fluorinated same dielectric same barrier	USPAT	2002/09/27 16:33
-	1	flac and fluorinated adj dielectric	USPAT	2002/09/27 16:33
-	5	flac and dielectric	USPAT	2002/09/27 16:35
-	136	carbon near3 polymer same (flac or fdlc or amorphous adj carbon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 16:37
-	103	carbon near3 polymer near6 (flac or fdlc or amorphous adj carbon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 16:37
-	93	carbon near3 polymer near3 (flac or fdlc or amorphous adj carbon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 18:20
-	57	fsg.ti,ab. and interconnect	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 19:33
-	2	(fluorinated adj silicon adj oxide or "sio:f") same dielectric adj layer same barrier adj layer same (tantalum or cobalt)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/27 19:35
-	12	fluorinated adj dielectric same (adhesion or adhesive) near2 layer same barrier	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 12:57

-	1	fluorine same barrier adj layer same (cobalt adj silicide or tantalum adj silicide or cobalt-silicon or tantalum-silicon or cobalt-tantalum-silicon or cobalt-tantalum adj silicide or cobalt adj cobalt-tantalum adj silicide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 13:21
-	0	fluorinated adj dielectric same barrier same (alternating or both adj side)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 13:23
-	0	fluorinated adj dielectric same barrier same (alternating or both adj side or sandwich\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 13:23
-	2	((("6284657") or ("5880018"))).PN.	USPAT	2002/09/28 15:29
-	0	(fluorinated near3 (dielectric or polyethylene or parylene or amorphous adj carbon or BPSG) or PTFE or PFCB or F-BPSG) near25 barrier near25 ((tantalum or cobalt) adj (silicide or silicon) or tantalum-silicon or cobalt-silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 15:38
-	0	(fluorinated near3 (dielectric or polyethylene or parylene or amorphous adj carbon or BPSG or boron adj phospho adj silicate adj glass or boron-phosph0 adj silicate adj glass or boron-phospho-silicate adj glass or silicon adj (oxide or dioxide)) or "sio:f" or PTFE or teflon or fsg or PFCB or F-BPSG) near25 barrier near25 ((tantalum or cobalt) adj (silicide or silicon) or tantalum-silicon or cobalt-silicon or tantalum-cobalt-silicon or cobalt-tantalum-silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 15:45
-	0	(fluorinated near3 (dielectric or polyethylene or parylene or amorphous adj carbon or BPSG or boron adj phospho adj silicate adj glass or boron-phosph0 adj silicate adj glass or boron-phospho-silicate adj glass or silicon adj (oxide or dioxide)) or "sio:f" or PTFE or teflon or fsg or PFCB or F-BPSG) near25 barrier near25 ((tantalum or cobalt) adj (silicide or silicon) or "tasi.sub.2" or tantalum-silicon or cobalt-silicon or tantalum-cobalt-silicon or cobalt-tantalum-silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 15:49
-	0	(fluorinated near6 (dielectric or polyethylene or parylene or amorphous adj carbon or BPSG or boron adj phospho adj silicate adj glass or boron-phosph0 adj silicate adj glass or boron-phospho-silicate adj glass or silicon adj (oxide or dioxide)) or "sio:f" or PTFE or teflon or fsg or PFCB or F-BPSG) near25 barrier near25 ((tantalum or cobalt) adj (silicide or silicon) or "tasi.sub.2" or tantalum-silicon or cobalt-silicon or tantalum-cobalt-silicon or cobalt-tantalum-silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 15:51

-	1	(fluorinated near6 (dielectric or polyethylene or parylene or amorphous adj carbon or BPSG or boron adj phospho adj silicate adj glass or boron-phospho adj silicate adj glass or boron-phospho-silicate adj glass or silicon adj (oxide or dioxide)) or "sio:f" or PTFE or teflon or fsg or PFCB or F-BPSG) same barrier same ((tantalum or cobalt) adj (silicide or silicon) or "tasi.sub.2" or "cosi.sub.2" or tasi or cosi or tantalum-silicon or cobalt-silicon or tantalum-cobalt-silicon or cobalt-tantalum-silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 17:33
-	0	double adj jet same precipitation same other adj methods	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 17:34
-	6321	precipitation adj2 "methods"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 17:35
-	853	precipitation adj2 "methods".ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 17:37
-	1	("4680612").PN.	USPAT	2002/09/28 17:38
-	1	("6232662").PN.	USPAT	2002/09/28 17:43
-	1	("6284657").PN.	USPAT	2002/09/28 17:43
-	1	("6294396").PN.	USPAT	2002/09/28 17:44
-	1	("5880018").PN.	USPAT	2002/09/28 17:44
-	0	("cmos adj inverter.ti,ab,clm.").PN.	USPAT	2002/09/28 18:43
-	103	(cmos adj inverter.ti,ab,clm.) and 257/\$6.ccls.	USPAT	2002/09/28 18:45
-	2	("6323555").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/01 16:03
-	0	("delarosa.in.").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/01 16:03
-	30	delarosa.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/01 18:48
-	1	fluorine adj diffusion adj barrier near12 (tantalum or ta)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/01 18:50
-	28	FSG.ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/02 09:31

-	2	FSG.ti. and fluorinated adj silicon adj glass	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/02 09:43
-	0	(("6284657").PN.) and cobalt	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/02 09:43
-	2	("6284657").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/02 11:26
-	2	("6294396").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/02 11:36
-	2	("6232662").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/02 13:13
-	2	("6017818").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/02 15:05
-	10	diffusion near3 barrier near12 (fluorine or F) and interconnect and polymer and silicon and (tantalum adj nitride or TaN) and (cobalt or cobalt adj silicide or Co or CoSi)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/02 15:16
-	0	diffusion near3 barrier near12 (fluorine or F) and interconnect and polymer adj3 (film or layer) and silicon and (tantalum adj nitride or TaN) near12 (cobalt or cobalt adj silicide or Co or CoSi)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/02 15:18
-	0	diffusion near3 barrier near12 (fluorine or F) and interconnect and polymer adj3 (film or layer) and (si or silicon) and (tantalum adj nitride or TaN) near12 (cobalt or cobalt adj silicide or Co or CoSi)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/02 15:18
-	116	titanium adj alloy near8 silicide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 11:26
-	17	titanium adj alloy near1 silicide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 11:26
-	36	titanium adj alloy near2 silicide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/03 12:03